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# United States Patent [19]

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## [54] METHOD OF FORMING A COATING FILM AND COATING APPARATUS

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Mar. 15, 1995	[JP]	Japan	.....	7-083207
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[51] Int. Cl.<sup>6</sup> ..... **B05B 13/02; B05C 11/00; B08B 3/00**

[52] U.S. Cl. .... **118/319; 118/52; 118/72; 134/53; 15/302**

[58] Field of Search ..... **118/52, 319, 320, 118/72, 73, 500; 134/902, 153, 435; 414/936, 940, 941; 901/27-29, 43; 15/77, 88.2, 88.3, 302**

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## [57] ABSTRACT

A method of forming a coating film, in which the coating film is formed by supplying a coating liquid onto a surface of a substrate, while the substrate housed in a processing vessel is rotated together with the processing vessel, includes the steps of coating the surface of the substrate with a solvent, supplying the coating liquid to the substrate, rotating the substrate and the processing vessel at a first rotation speed to diffuse the coating liquid on the surface of the substrate, closing the processing vessel with a lid to seal the substrate in the processing vessel, and rotating the processing vessel with the lid and the substrate at a second rotation speed to uniform a film thickness of the coating film.

**38 Claims, 32 Drawing Sheets**

